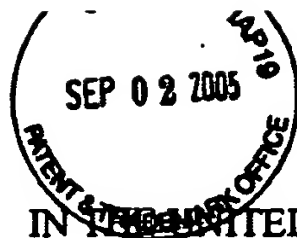


09/927,102



-1-

PATENT

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9/2/05

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION
METROLOGY SYSTEM
INTEGRATED INTO
SEMICONDUCTOR WAFER
PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

**RESPONSE TO FINAL OFFICE ACTION
MAILED MARCH 9, 2005**

353 Sacramento St., Suite 2200
San Francisco, CA 94111
(415) 772-4900

M/S RCE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited
with the United States Postal Service as First Class Mail in an
envelope, addressed to: Commissioner for Patents, P.O.
Box 1450, Alexandria, VA 22313-1450 on August 31, 2005.
STALLMAN & POLLOCK LLP

Dated: 08/31/2005

By:

Georgia K. Stith
Georgia K. Stith

Sir:

In response to the **Final Office Action** mailed March 9, 2005, and in accordance with the
accompanying **Request for Continued Examination and Petition for Extension of Time**,
please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this
paper.

Remarks/Arguments begin on page 7 of this paper.

09/06/2005 YPOLITE1 00000054 09927102

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Atty Docket No.: TTI-31000